

[54] OXIDE WALLED EMITTER

[75] Inventors: Toyoki Takemoto, Kyoto; Tsutomu Fujita, Osaka; Hiroyuki Sakai, Osaka; Haruyasu Yamada, Osaka, all of Japan

[73] Assignee: Matsushita Electric Industrial Co., Ltd., Osaka, Japan

[21] Appl. No.: 542,555

[22] Filed: Oct. 17, 1983

Related U.S. Application Data

[63] Continuation of Ser. No. 231,460, Feb. 4, 1981, abandoned.

[51] Int. Cl.³ H01L 27/04; H01L 29/04; H01L 29/72

[52] U.S. Cl. 357/50; 357/34; 357/55; 357/59; 357/20

[58] Field of Search 357/50, 55, 89, 34, 357/20

[56] References Cited

U.S. PATENT DOCUMENTS

4,160,991 7/1979 Anantha et al. 357/50

4,214,315 7/1980 Anantha et al. 357/50
4,231,819 11/1980 Raffel et al. 357/50
4,255,207 3/1981 Nicolay et al. 357/55
4,269,636 5/1981 Rivoli et al. 357/55
4,318,751 3/1982 Horng 357/50

OTHER PUBLICATIONS

Cosand, "Very High Speed . . . Bipolar . . .", IEEE International Electron Dev. Meeting, Technical Digest, Dec. 1973, pp. 35-37.

Primary Examiner—William D. Larkins

Assistant Examiner—Charles S. Small, Jr.

Attorney, Agent, or Firm—Burgess, Ryan and Wayne

[57] ABSTRACT

A semiconductor integrated circuit device in which the side surfaces of an emitter of an oxide isolated bipolar transistor are surrounded with insulating compounds or regions so that the capacitance between the emitter and base is lowered and a base is formed by the self-alignment so that the influence of an active base between an external base and the emitter can be made negligible. Thus the base resistance and parasitic capacitance are lowered.

7 Claims, 21 Drawing Figures

